

Roll No.:.....

# *National Institute of Technology, Delhi*

Name of the Examination: B. Tech

Branch : ECE

Semester : III

Title of the Course : Solid State Devices

Course Code : ECB 201

Time: 3 Hours

Maximum Marks: 50

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- Questions are printed on BOTH sides. Answers should be CLEAR AND TO THE POINT.
  - All parts of a single question must be answered together. ELSE QUESTION SHALL NOT BE EVALUATED.
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## Section A

Choose the appropriate answer and write on the answer sheet only.

1. (a) Common base current gain can be increased by enhancing the **injection efficiency/ base transport factor/both of the above.** [1x10=10]  
(b) Carrier recombination in E-B depletion region **increases/ decreases** injection efficiency.  
(c) As reverse bias increases, collector current **increases/ decreases/ remains same.**  
(d) Emitter injection efficiency **increases/ decreases** with increase in doping concentration at E region.  
(e) Lower base doping **increases/ decreases** base current.  
(f) BJT Operation is controlled by carrier transport in base through **diffusion/drift** process.  
(g) Quantum mechanics is supported by **Schrödinger equation/ Poisson's equation/ Shockley equation.**  
(h) With a phase shift of 90°, Lissajous figure at CRO will produce an **ellipse/ circle/ trapezoid.**  
(i) In a CRO in sweep rate frequency is 100 Hz with 2 full sinusoidal cycles observed, then frequency of the input vertical voltage will be **100 Hz/ 200 Hz/ 1000Hz.**  
(j) At pinch-off situation of a JFET, pinch-off voltage refers to the corresponding **gate-source voltage/ drain source voltage/ gate- drain voltage.**

## Section B

Write brief note on following:

2. (a) Thermal runaway  
(b) Base width narrowing and early effect.  
(c) Depletion mode MOSFET  
(d) Tunnel diode  
(e) Hall effect

[2x5=10]

### Section C

3. In a very long p-type Si bar with area =  $0.5 \text{ cm}^2$  and  $N_a = 10^{17}/\text{cm}^3$ , holes are injected such that steady state excess hole concentration becomes  $5 \times 10^{16}/\text{cm}^3$  at  $x=0$ . What is the separation between  $E_{Fp}$  (Quasi Fermi Level for holes) and  $E_c$  at  $x=1000\text{\AA}$ ? [ $\mu_p = 500 \text{ cm}^2/\text{V}\cdot\text{sec}$ ,  $E_g = 1.1\text{eV}$ ] [3]
4. (a) An n-type Si semiconductor sample having with equilibrium carrier concentration,  $n_0 = 10^{14}/\text{cm}^3$ . After steady shining of light, let optically generated EHP's are  $10^{13} \text{ EHP}/\text{cm}^3/\mu\text{s}$  when  $\tau_n = \tau_p = 1\mu\text{s}$ . Calculate total  $e^-$  and hole concentrations after shining of light. [ $n_i = 1.5 \times 10^{10}/\text{cm}^3$ ] [5]  
 (b) Find the positions of Quasi-Fermi levels with respect to intrinsic energy level. Draw the energy band diagram.
5. A cylindrical Si bar has 1mm length and  $0.1 \text{ mm}^2$  cross-section. Find conductivity and resistances for Si (ignoring minority carriers) for following cases: [2]  
 (a) When pure  
 (b) When doped with  $10^{16}/\text{cm}^3$  donors. [ $\mu_n = 1500 \text{ cm}^2/\text{V}\cdot\text{S}$ ,  $\mu_p = 500 \text{ cm}^2/\text{V}\cdot\text{S}$ ,  $n_i = 1.5 \times 10^{10}/\text{cm}^3$ ]
6. Sketch and label energy band diagrams across the Metal-Semiconductor Junction of all following cases (after contact only). [ $q\chi = 4.0 \text{ eV}$ ,  $E_g = 1.1\text{eV}$ ,  $KT = 0.026\text{eV}$ ,  $n_i = 1.5 \times 10^{10}/\text{cm}^3$  at 300k for Si] [7]  
 (a)  $q\phi_m = 4.5\text{eV}$ ,  $q\phi_m = 2\text{eV}$  for n-type for  $V = 0\text{V}$ ,  $0.2\text{V(FB)}$ ,  $+1\text{V(RB)}$   
 (b) Depletion width (if any) for above cases:
7. Consider a Si p-n junction diode of area  $10^{-4} \text{ cm}^2$  at 300k. [3]  
 For p-type part:  $N_a = 2.5 \times 10^{15}/\text{cm}^3$   
 $\tau_n = 10^{-6} \text{ s}$   
 $\mu_n = 1350 \text{ cm}^2/\text{V}\cdot\text{s}$   
 For n-type part:  $N_d = 5 \times 10^{16}/\text{cm}^3$   
 $\tau_p = 10^{-7} \text{ s}$   
 $\mu_p = 325 \text{ cm}^2/\text{V}\cdot\text{s}$   
 $n_i = 1.5 \times 10^{10}/\text{cm}^3$   
 (a) Express  $I_0$  (Reverse Saturation Current) in terms of above diode parameters and then calculate its value.  
 (b) Calculate total current (I) for FB of 0.6V.

### Section D

8. Explain in detail the transistor amplification process with the help of graphical analysis. [3]
9. What is the implication of p-i-n diode? How it overcomes the disadvantages of p-n diode? [2]
10. Define JFET parameters? [3]
11. Discuss briefly the formation of energy bands in an multiatomic crystal lattice. [2]

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### Useful Equations

Fermi-Dirac  $e^-$  distribution:  $f(E) = \frac{1}{e^{(E-E_F)/kT} + 1} \approx e^{(E_F-E)/kT}$  for  $E \gg E_F$

Equilibrium:  $n_0 = \int_{E_c}^{\infty} f(E)N(E)dE = N_c f(E_c) = N_c e^{-(E_c-E_F)/kT}$

$$N_c = 2 \left( \frac{2\pi m_n^* kT}{h^2} \right)^{3/2} \quad N_v = 2 \left( \frac{2\pi m_p^* kT}{h^2} \right)^{3/2} \quad \begin{matrix} n_0 = n_i e^{(E_F-E_c)/kT} \\ p_0 = n_i e^{(E_v-E_F)/kT} \end{matrix} \quad n_i p_0 = n_i^2$$

$$p_0 = N_v [1 - f(E_v)] = N_v e^{-(E_F-E_v)/kT}$$

$$n_i = N_c e^{-(E_c-E_F)/kT}, \quad p_i = N_v e^{-(E_F-E_v)/kT}, \quad n_i = \sqrt{N_c N_v} e^{-E_g/2kT} = 2 \left( \frac{2\pi kT}{h^2} \right)^{3/2} (m_n^* m_p^*)^{3/4} e^{-E_g/2kT}$$

$$n = N_c e^{-(E_c-F)/kT} = n_i e^{(F-E_c)/kT}$$

$$p = N_v e^{-(F-E_v)/kT} = n_i e^{(E_v-F)/kT}$$

$$np = n_i^2 e^{(F-E_c-E_v)/kT}$$

$$\frac{d\mathcal{E}(x)}{dx} = -\frac{d^2V(x)}{dx^2} = \frac{\rho(x)}{\epsilon} = \frac{q}{\epsilon} (p - n + N_d^+ - N_a^-) \quad \mathcal{E}(x) = -\frac{dV(x)}{dx} = \frac{1}{q} \frac{dE_i}{dx}$$

$$\frac{I_x}{A} = J_x = q(n\mu_n + p\mu_p)\mathcal{E}_x = \sigma \mathcal{E}_x$$

Diffusion length:  $L = \sqrt{D\tau}$  Einstein relation:  $\frac{D}{\mu} = \frac{kT}{q}$

Continuity:  $\frac{\partial p(x,t)}{\partial t} = \frac{\partial \delta p}{\partial t} = -\frac{1}{q} \frac{\partial J_p}{\partial x} - \frac{\delta p}{\tau_p} \quad \frac{\partial n}{\partial t} = \frac{1}{q} \frac{\partial J_n}{\partial x} - \frac{\delta n}{\tau_n}$

For steady state diffusion:  $\frac{d^2 \delta n}{dx^2} = \frac{\delta n}{D_n \tau_n} = \frac{\delta n}{L_n^2} \quad \frac{d^2 \delta p}{dx^2} = \frac{\delta p}{L_p^2}$

Equilibrium:  $V_0 = \frac{kT}{q} \ln \frac{p_p}{p_n} = \frac{kT}{q} \ln \frac{N_a}{n_i^2/N_d} = \frac{kT}{q} \ln \frac{N_d N_a}{n_i^2} \quad \frac{p_p}{p_n} = \frac{n_n}{n_p} = e^{qV_0/kT} \quad W = \left[ \frac{2\epsilon(V_0 - V)}{q} \left( \frac{N_a + N_d}{N_d N_a} \right) \right]^{1/2}$

Junction Depletion:  $C_j = \epsilon A \left[ \frac{q}{2\epsilon(V_0 - V)} \frac{N_d N_a}{N_d + N_a} \right]^{1/2} = \frac{\epsilon A}{W}$



One-sided abrupt  $p^+n$ :  $x_{mi} = \frac{WN_d}{N_a + N_d} \approx W$

$$V_0 = \frac{qN_d W^2}{2\epsilon}$$

$$\Delta p_n = p(x_{mi}) - p_n = p_n(e^{qV/kT} - 1)$$

$$\delta p(x_n) = \Delta p_n e^{-x_n/L_p} = p_n(e^{qV/kT} - 1)e^{-x_n/L_p}$$

Ideal diode:  $I = qA\left(\frac{D_p}{L_p}p_n + \frac{D_n}{L_n}n_p\right)(e^{qV/kT} - 1) = I_0(e^{qV/kT} - 1)$

Stored charge

exp. hole dist.:  $Q_p = qA \int_0^\infty \delta p(x_n) dx_n = qA \Delta p_n \int_0^\infty e^{-x_n/L_p} dx_n = qAL_p \Delta p_n$

$$I_p(x_n = 0) = \frac{Q_p}{\tau_p} = qA \frac{L_p}{\tau_p} \Delta p_n = qA \frac{D_p}{L_p} p_n (e^{qV/kT} - 1)$$

$$I_{Ep} = qA \frac{D_p}{L_p} \left( \Delta p_E \tanh \frac{W_b}{L_p} - \Delta p_C \operatorname{csch} \frac{W_b}{L_p} \right)$$

$$I_C = qA \frac{D_p}{L_p} \left( \Delta p_E \operatorname{csch} \frac{W_b}{L_p} - \Delta p_C \tanh \frac{W_b}{L_p} \right) \quad \text{Substrate bias: } \Delta V_T \approx \frac{\sqrt{2\epsilon_s q N_a}}{C_i} (-V_B)^{1/2}$$

Oxide:  $C_i = \frac{\epsilon_i}{d}$     Depletion:  $C_d = \frac{\epsilon_s}{W}$     MOS:  $C = \frac{C_i C_d}{C_i + C_d}$

Inversion:  $\phi_i(\text{inv.}) = 2\phi_F = 2 \frac{kT}{q} \ln \frac{N_a}{n_i}$  (6-15)     $W = \left[ \frac{2\epsilon_s \phi_i}{q N_a} \right]^{1/2}$

$$Q_d = -qN_d W_m = -2(\epsilon_s q N_a \phi_F)^{1/2} \quad (6-32) \quad \text{At } V_{FB}: C_{FB} = \frac{C_i C_{dchye}}{C_i + C_{dchye}}$$

$$\Delta p_E = p_n (e^{qV_{EB}/kT} - 1)$$

$$\Delta p_C = p_n (e^{qV_{CB}/kT} - 1)$$

$$I_B = qA \frac{D_p}{L_p} \left[ (\Delta p_E + \Delta p_C) \tanh \frac{W_b}{2L_p} \right]$$

$$B = \frac{I_C}{I_{Ep}} = \frac{\operatorname{csch} W_b/L_p}{\tanh W_b/L_p} = \operatorname{sech} \frac{W_b}{L_p} \approx 1 - \left( \frac{W_b^2}{2L_p^2} \right)$$

(Base transport factor)

$$\gamma = \frac{I_{Ep}}{I_{Ep} + I_{Ep}} = \left[ 1 + \frac{L_p^2 n_i \mu_n^p}{L_p^2 p_n \mu_p^p} \tanh \frac{W_b}{L_p} \right]^{-1} = \left[ 1 + \frac{W_b n_i \mu_n^p}{L_p^2 p_n \mu_p^p} \right]^{-1}$$

(Emitter injection efficiency)

$$\frac{i_C}{i_E} = B\gamma \approx \alpha \quad (7-3)$$

$$\frac{i_C}{i_B} = \frac{B\gamma}{1 - B\gamma} = \frac{\alpha}{1 - \alpha} \approx \beta \quad \left( \frac{i_C}{i_B} = \beta = \frac{\tau_p}{\tau_n} \right)$$

(Common base gain)

(Common emitter gain)

(For  $\gamma = 1$ )